Batch production

Beneq P800

OVERVIEW



The Beneq P800 is a production-proven batch ALD system perfect for industrial manufacturing. Boasting a vacuum chamber with a diameter of 800 mm, this tool provides ample space for high volume coating production while still providing excellent batch uniformity. It is ideal for depositing thick optical coatings and etch-resistant barrier films.

FEATURES

Size

Coat parts with diameters larger than 600 mm or use the P800's capacity to easily scale up your batch size of smaller parts without compromising film quality and uniformity.

Flexibility

The P800 offers customizable reaction chamber sizes optimized for your substrate and application. Reaction chambers are easily switchable for easy maintenance and maximum tool uptime.

Robustness

The P800 is equipped with high-capacity precursor sources, deactivation and filtration systems to enable easy deposition of micron-thick film stacks.

Substrate examples

- Semiconductor chamber lids, liners, showerheads
- Printed circuit boards
- Large optical domes and freeform optics.

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SPECIFICATIONS

Process type	Thermal ALD
Integration	Stand-alone
Dimensions (L x W x H)	3200 x 1340 x 2460 mm
Vacuum chamber dimensions	800 mm
Temperature range	25-550 °C
Substrate type	• Wafers • Glass or metal sheets • 3D and freeform parts
Substrate space	• 550 x 310 x 700 mm • 730 x 1200 x 10 mm

BATCH PRODUCTION EQUIPMENT

Beneq’s P-series provides the largest-scale, general-purpose ALD production systems ideal for coating diverse substrate types and thick films. It is easy to scale up ALD deposition from the R&D phase to full manufacturing workflows.



Beneq P400A

Large scale, general purpose ALD production systems ideal for coating diverse substrate types and thick films.



Beneq P1500

The world’s largest ALD reactor uniquely designed for coating very wide area sheets, lenses, and 3D components.